## Ting Sun

List of Publications by Year in descending order

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TINC SUN

#	Article	IF	CITATIONS
1	Effect of Na Promoter on Fe-Based Catalyst for CO <sub>2</sub> Hydrogenation to Alkenes. ACS Sustainable Chemistry and Engineering, 2019, 7, 925-932.	6.7	117
2	Mn decorated Na/Fe catalysts for CO <sub>2</sub> hydrogenation to light olefins. Catalysis Science and Technology, 2019, 9, 456-464.	4.1	96
3	Promoted effect of alkalization on the catalytic performance of Rh/alk-Ti 3 C 2 X 2 (X O, F) for the hydrodechlorination of chlorophenols in base-free aqueous medium. Applied Catalysis B: Environmental, 2017, 210, 462-469.	20.2	77
4	Nitrogen-Doped Carbon-Stabilized Ru Nanoclusters as Excellent Catalysts for Hydrogen Production. ACS Sustainable Chemistry and Engineering, 2019, 7, 1178-1184.	6.7	65
5	Magnetic, recyclable Pt <sub>y</sub> Co <sub>1â^'y</sub> /Ti <sub>3</sub> C <sub>2</sub> X <sub>2</sub> (X = O, F) catalyst: a facile synthesis and enhanced catalytic activity for hydrogen generation from the hydrolysis of ammonia borane. New Journal of Chemistry, 2017, 41, 2793-2799.	2.8	61
6	Highly selective gas sensing properties of partially inversed spinel zinc ferrite towards H2S. Sensors and Actuators B: Chemical, 2016, 235, 258-262.	7.8	53
7	Investigating the effect of diamond size and conditioning force on chemical mechanical planarization pad topography. Microelectronic Engineering, 2010, 87, 553-559.	2.4	40
8	Efficient hydrogen evolution from ammonia borane hydrolysis with Rh decorated on phosphorus-doped carbon. International Journal of Hydrogen Energy, 2019, 44, 16548-16556.	7.1	38
9	Investigating Effect of Conditioner Aggressiveness on Removal Rate during Interlayer Dielectric Chemical Mechanical Planarization through Confocal Microscopy and Dual Emission Ultraviolet-Enhanced Fluorescence Imaging. Japanese Journal of Applied Physics, 2010, 49, 026501.	1.5	31
10	Investigation of eccentric PVA brush behaviors in post-Cu CMP cleaning. Microelectronic Engineering, 2012, 100, 20-24.	2.4	25
11	Optical and Mechanical Characterization of Chemical Mechanical Planarization Pad Surfaces. Japanese Journal of Applied Physics, 2010, 49, 046501.	1.5	20
12	Synergistic catalysis of Pd–Ni(OH)2 hybrid anchored on porous carbon for hydrogen evolution from the dehydrogenation of formic acid. International Journal of Hydrogen Energy, 2020, 45, 12849-12858.	7.1	20
13	Frictional Analysis of Various Poly(vinyl alcohol) Brush Roller Designs for Post-Interlevel Dielectric CMP Scrubbing Applications. Electrochemical and Solid-State Letters, 2009, 12, H84.	2.2	17
14	Phase transition, piezoelectric, and multiferroic properties of La(Co <sub>0.5</sub> Mn <sub>0.5</sub> )O <sub>3</sub> -modified BiFeO <sub>3</sub> -BaTiO <sub>3</sub> lead-free ceramics. Physica Status Solidi (A) Applications and Materials Science, 2015, 212, 2012-2022.	1.8	15
15	Maximizing hydrogen production by AB hydrolysis with Pt@cobalt oxide/N,O-rich carbon and alkaline ultrasonic irradiation. Inorganic Chemistry Frontiers, 2022, 9, 2204-2212.	6.0	13
16	Tunable magnetic pole inversion in multiferroic BiFeO <sub>3</sub> –DyFeO <sub>3</sub> solid solution. Journal of Materials Chemistry C, 2017, 5, 4063-4067.	5.5	12
17	Effect of Various Cleaning Solutions and Brush Scrubber Kinematics on the Frictional Attributes of Post Copper CMP Cleaning Process. Solid State Phenomena, 0, 145-146, 363-366.	0.3	8
18	Improved piezoelectric and bright up-conversion photoluminescent properties in Ho-doped Bi0.5Na0.5TiO3–BaTiO3 lead-free ceramics. Journal of Materials Science: Materials in Electronics, 2015, 26, 6979-6985.	2.2	8

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19	Removal of linear and monobranched alkane from aviation gasoline by 5A zeolite adsorption for octane number enhancement. Canadian Journal of Chemical Engineering, 2016, 94, 128-133.	1.7	8
20	Method for Determining the Lubrication Mechanism of Post-ILD CMP Brush Scrubbing. Electrochemical and Solid-State Letters, 2008, 11, H214.	2.2	4
21	Brush Scrubbing for Post-CMP Cleaning. , 2017, , 109-133.		1